Amendment

A1126/T08910

016301-008910US

DEC 2 0 2000

V. RAVI et al In re application of: KRAMAD!

Application No.: 09/362.504 Filed: July 27, 1999

Group Art Unit: 1763

For: METHOD FOR REDUCING THE INTRINSIC STRESS

OF HIGH DENSITY PLASMA FILMS

THE ASSISTANT COMMISSIONER FOR PATENTS

Washington, D.C. 20231

December 15, 2000

I hereby certify that this is being deposited with the United States Postal Service as first class mail in an envelope addressed to:

Assistant Commissioner for Patents

Washington, D.C. 20231

RESPONSE TO OFFICE ACTION UNDER 37 C.F.R. § 1.116 EXPEDITED PROCEDURE-EXAMINING GROUP 1763

Sir:

Transmitted herewith is an amendment in the above-identified application.

If any extension of time is needed, then this response should be considered a petition therefor.

The filing fee has been calculated as shown below:

(Col. 1)

(Col. 2)

(Col. 3)

SMALL ENTITY

OTHER THAN **SMALL ENTITY**

	CLAIMS REMAINING AFTER AMENDMENT		HIGHEST NO. PREVIOUSLY PAID FOR		ESENT XTRA	
TOTAL	* 21	MINUS	** 21	=	0	
INDEP.	* 5	MINUS	*** 5	=	0	
[] FIRST PRESENTATION OF MULTIPLE DEP. CLAIM						

RATE	ADDIT. FEE
x \$9.00 =	
x \$40.00 =	
+ \$135.00 =	
TOTAL ADDIT. FEE	

RATE ADDIT. OR FEE x \$18.00 =\$0.00 x \$80.00 =\$0.00 + \$270.00 = OR TOTAL \$0.00

[X]No fee is due.

Please charge Deposit Account No. 20-1430 as follows:

Claims fee

Any additional fees associated with this paper or during the pendency of this application, [X]

NO extra copies of this sheet are enclosed.

PLEASE ADDRESS ALL CORRESPONDENCE TO:

PATENT COUNSEL

APPLIED MATERIALS, INC.

P.O. BOX 450A

SANTA CLARA, CA 95052

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I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail i

DEC 2 0 2000

Assistant Commissioner for Paten

Washington, D.C. 20231

TOWNSFIND and TOWNSFIND and CREW LLP

RESPONSE TO OFFICE ACTION **UNDER 37 CFR 1.116 EXPEDITED** PROCEDURE - EXAMINING GROUP 1763

Attorney Docket No.: A1126/T08910 TTC Reference No.: 16301-008910

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

KRAMADHATI V. RAVI et al.

Application No.: 09/362,504

Filed: July 27, 1999

For: METHOD FOR REDUCING THE

INTRINSIC STRESS OF HIGH DENSITY PLASMA FILMS

Examiner:

Rudy Zervigon

RESPONSE TO OFFICE ACTION UNDER 37 CFR 1.116 EXPEDITED PROCEDURE

EXAMINING GROUP 1763

Box AF

Assistant Commissioner for Patents Washington, D.C. 20231

Sir:

In response to the Final Office Action mailed October 27, 2000, please reconsider this application in view of the following comments.

IN THE CLAIMS:

The claims are unamended, but are reproduced below for the Examiner's convenience and reference.

- An integrated circuit formed on a semiconductor substrate by the 16. method of:
 - flowing a process gas into a substrate processing chamber; a)